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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet	1	of	1
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Complete If Known

Application Number	10,724,113
Filing Date	December 1, 2003
First Named Inventor	Moshe FINAROV et al.
Group Art Unit	2077 2886
Examiner Name	- R. Punnoose
Attorney Docket Number	FINAROV=3A

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

**Examiner
Signature**

/Roy Punnoose/

Date Considered

04/01/2007

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Sheet 2	of 2	Attorney Docket Number	FINAROV=3A

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
RP	AH	N. CHATEAU et al, "Algorithm for the rigorous coupled-wave analysis of grating diffraction", <i>Journal of the Optical Society of America A</i> , vol. 11, no. 4, April 1994, pp 1321-1331	
	AI	T. GAYLORD et al, "Analysis and Applications of Optical Diffraction by Gratings", <i>Proceedings of the IEEE</i> , vol. 73, no. 5, May 1985, pp 894-938	
	AJ	E. GLYTSIS et al, "Review of rigorous coupled-wave analysis and of homogeneous effective medium approximations for high spatial-frequency surface-relief gratings", <i>Conference on Binary Optics</i> , February 23-25, 1993, pp 62-76	
	AK	E. GLYTSIS et al, "Rigorous coupled-wave analysis and applications of rating diffraction", <i>Diffraction and Miniaturized Optics, Critical Reviews of Optical Science and Technology</i> , Vol. CR49, 12-13 July 1993, pp 3-31	
	AL	R. KRUKAR et al, "Overlay and grating line shape metrology using optical scatterometry: final report", August 31, 1993, <i>DARPA, U. S. Army Missile Command</i> , p.28	
	AM	R. KRUKAR et al, "Reactive ion etching profile and depth characterization using standard and neutral network analysis of light scattering data", <i>J. Appl. Phys.</i> Vol. 74, No. 6, 15 September 1993	
	AN	S. LEE et al, "More stable algorithm for rigorous coupled wave analysis applied to topography simulation in optical lithography and its numerical implementation", <i>Optical Microlithography IX, SPIE</i> , vol. 2726, 13-15 March 1996, pp 288-298	
	AO	J.M. LENG et al, "Simultaneous measurement of six layers in a silicon on insulator film stack using spectrophotometry and beam profile reflectometry", <i>Journal of Applied Physics</i> , vol. 81, No.8, Apr. 1997, pp 3570-3578	
	AP	D. MILLS et al, "Spectral ellipsometry on patterned wafers", <i>Process, Equipment, and Materials Control in Integrated Circuit Manufacturing, SPIE</i> vol. 2637, 25-26 October 1995, pp 194-203	
	AQ	S. PENG et al, "Efficient implementation of rigorous coupled-wave analysis for surface-relief gratings", <i>J. Opt. Soc. Am. A</i> , vol. 12, no. 5, May 1995, pp 1087-1096	
	AR	D. ZIGER et al, "Linesize effects on ultraviolet reflectance spectra", <i>Optical Engineering</i> , January 1997, vol. 36, no. 1, pp 243-250	
RP	AS	Z. ZYLBERBERG et al, "Rigorous coupled-wave analysis of pure reflection gratings", <i>J. Opt. Soc. Am.</i> , vol. 73, no. 3, March 1983, pp 392-398	

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¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Complete if Known

Application Number	09/610,889
Filing Date	July 6, 2000
First Named Inventor	FINAROV et al.
Group Art Unit	2077 2886
Examiner Name	R. Punnoose
Attorney Docket Number	FINAROV=3

Sheet	1	of	2
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	AJ	VOSKOVTSOVA et al., <u>Soviet Journal of Optical Technology</u> , (1993) vol.60, no.9, pp.617-619	
	AK	ROGER et al., "Inverse scattering method in electromagnetic optics: Applications to diffraction grating", <u>J. Opt. Soc. Am.</u> , (1980), vol.70, No. 12, pp.1483-1495, Optical Society of America	
	AL	ROGER et al., "The perfectly conducting grating from the point of view of inverse diffraction", <u>Optica Acta</u> , (1979), vol.26, No. 4, pp.447-460, Taylor & Francis Ltd.	
	AM	ROGER et al., "Grating Profile Reconstruction by an Inverse Scattering Method" <u>Optics Communication</u> , (1980), vol.35, No.3, pp.299-302	
	AN	LOCHBIHLER et al., "Reconstruction of the profile of gold wire gratings: A comparison of different methods", <u>Optik</u> , (1994), vol.98, No.1, pp.21-25, Germany	
	AO	SAVITSKII et al., "Efficiency optimization of reflecting diffraction gratings with a trapezoidal groove profile", <u>Opt. Spectrosc.</u> , (1985), vol.59, No.2, pp.251-254, The Optical Society of America	
	AP	SPIKHAL'SKII, "Radiative Bragg Mirrors: Spectral Characteristics Versus Grating Groove Profile", <u>Optics Communication</u> , (1986), vol.57, No. 6, pp.375-379, Holland	
	AQ	NAQVI et al., "Etch depth estimation of large-period silicon grating with multivariate calibration of rigorously simulated diffraction profile", <u>Journal of the Optical Society of America</u> , (1994), vol.11, No.9, pp.2485-2493, Optical Society of America	
	AR	MOHARAM et al., "Rigorous coupled-wave analysis of planar-grating diffraction", <u>Journal of the Optical Society of America</u> , (1981), vol.71, No. 7, pp.811-818, Optical Society of America	
	AS	RAYMOND et al., "Resist and etched line profile characterization using scatterometry", <u>SPIE</u> , (1997), vol.3050, pp.476-486	

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09/610,889

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July 6, 2000

First Named Inventor	Moshe FINAROV
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Moshe FINAROV

Group Art Unit	2877	2886
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~~2877~~ 2886

Examiner Name

R. Punnoose

Attorney Docket Number

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